



Hitachi

S-4700-II

Process Type: FA SEMs/TEMs/Dual Beams

Date of Manufacture: 2001

Specification:

Secondary electron image resolution:

2.1nm at 1kV
1.5nm at 15kV and WD = 12mm or X-ray
analysis position

Backscattered electron image resolution

3.0nm at 15kV with YAG detector option

Magnification:

LM mode: 20 ~ 2,000X
HM mode: 100 ~ 800,000X

Specimen Stage:

Type II: X: 0 ~ 100mm; Y: 0 ~ 50mm; Z: 1.5 ~ 30mm; T: -5 ~ +60 deg, R: 360 deg.
Trackball operation
Full 5 axis motorization

Operating System: Windows XP
Vacuum: Diffusion Pump